Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	6392	(immers\$3 or wet\$4) near3 (patterning or \$5mask or reticle) .	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 15:40
L2	2370	1 not wet adj etch\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 12:39
L3	2033	2 not ink	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 13:35
L4	12	("3405614" "3508808" "3776616" "3802762" "3814943").PN. OR ("4008967"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/07/06 14:18
L5	10755	(inspect\$3 or (sens\$3 or detect\$3 or measur\$5 or determin\$3) near4 width near3 (feature or structure or pattern or line)) with (\$5mask or reticle or patterning near2 device)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 15:34
L6	156	1 and L5	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 14:39
L7	58	asml.asn. and (diffus\$3 not (trap\$4 or contamination or particle))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 14:45
L8	53	asml.asn. and diffuser	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 14:46

			T	T		T
L9	5	asml.asn. and diffuser with liquid	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 14:52
L11	64	asml.asn. and liquid with (part near2 (projection or system or apparatus or patterning))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2007/07/06 14:55
L12	1420	scan\$4 near3 (stage or table) same (second near2 (stage or table) or carrier near3 (plate or stage or table or base))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 15:14
L13	31	5 and 12	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 15:14
L14	17	("4085330" "4099055" "4256778" "4357540" "4365163" "4503329" "4514638" "4578587" "4683378" "4698236" "4751169" "4814615").PN. OR ("4958074").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/07/06 15:21
·L15	2543	(inspect\$3 or (sens\$3 or detect\$3 or measur\$5 or determin\$3) near4 width near3 (feature or structure or pattern or line)) with (\$5mask or reticle or patterning near2 device). ti,.clm.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 15:38
L16	1882	(inspect\$3 or (sens\$3 or detect\$3 or measur\$5 or determin\$3) near4 width near3 (feature or structure or pattern or line)) near3 (\$5mask or reticle or patterning near2 device). ti,.clm.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 15:38
L17	21	16 and (immers\$3 or wet\$4 or liquid) near3 (patterning or \$5mask or reticle)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 15:40

7/6/07 4:18:12 PM Page 2
C:\Documents and Settings\DRutledge\My Documents\EAST\workspaces\10711424 liquid btwn mask and lens meas width feature on mi

110	4270	255/72 75 ccls	LIC-DCDLIB.	OR	ON	2007/07/06 16:09
L18	4278	355/72,75.ccls.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OK		2007/07/00 10:09
L19	13	355/72,75.ccls. and vibrationally near4 (decoupl\$3 or isolat\$3) with (stage or table or carrier or support\$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 16:11
S1	5344	(immers\$3 or liquid) with (patterning or \$5mask or reticle) with (objective or lens or element or projection)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 12:26
S2	4621	(immers\$3 or liquid) near2 (patterning or \$5mask or reticle)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 11:27
S3	10755	(inspect\$3 or (sens\$3 or detect\$3 or measur\$5 or determin\$3) near4 width near3 (feature or structure or pattern or line)) with (\$5mask or reticle or patterning near2 device)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 11:30
S4	555	(S1 or S2) and S3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 11:31
S5	30	(immers\$3 or liquid) near2 (patterning or \$5mask or reticle) near2 surface with (objective or lens or element or projection)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 11:37
S6	0	(immers\$3 or liquid) near2 (space or gap) near3 (patterning or \$5mask or reticle) near2 surface with (objective or lens or element or projection)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 11:38

S7	11	(immers\$3 or liquid) with (space or gap) with (patterning or \$5mask or reticle) near2 surface with (objective or lens or element or projection)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 11:38
S8	41	S5 or S7	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/06 11:38